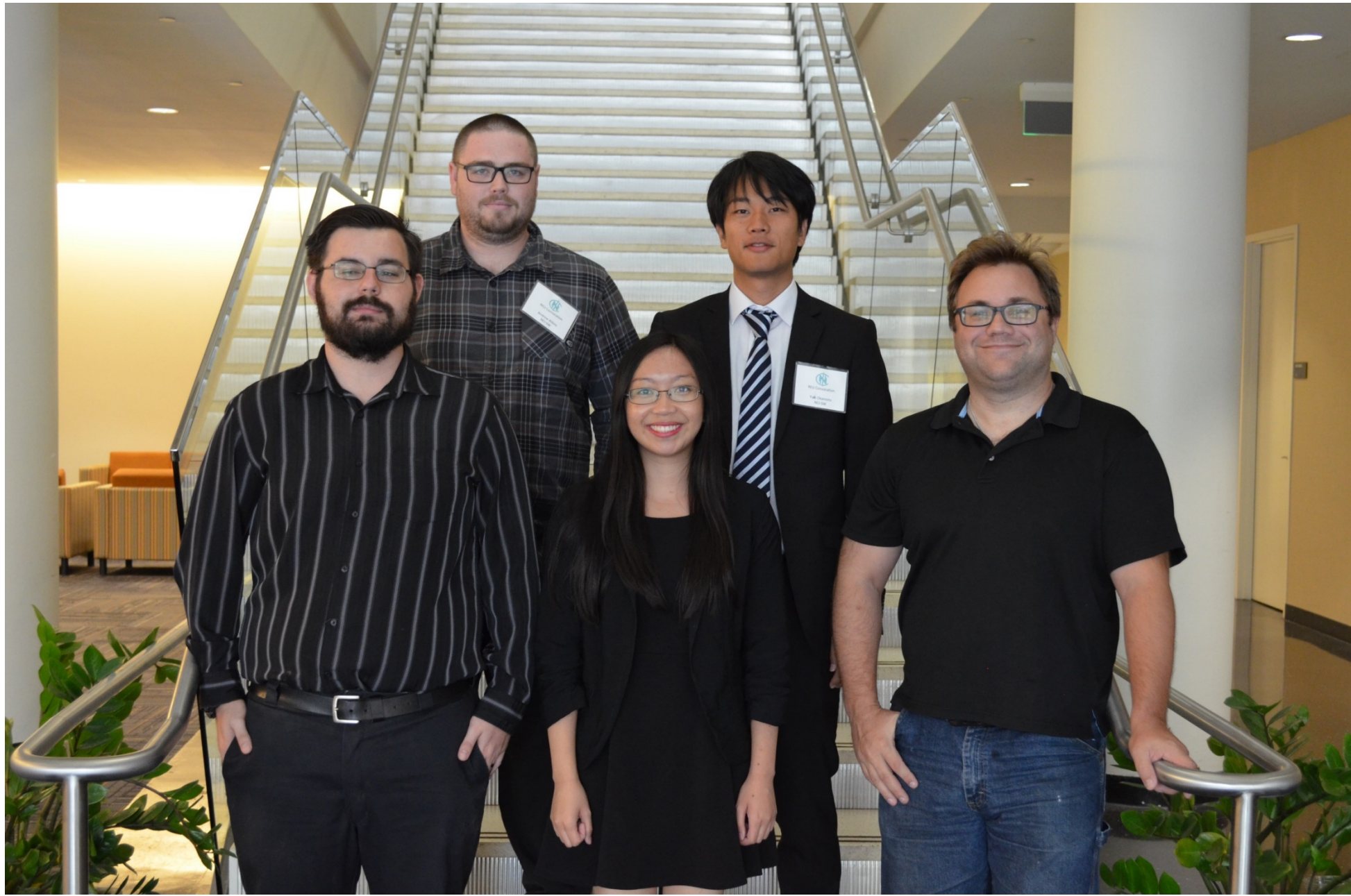


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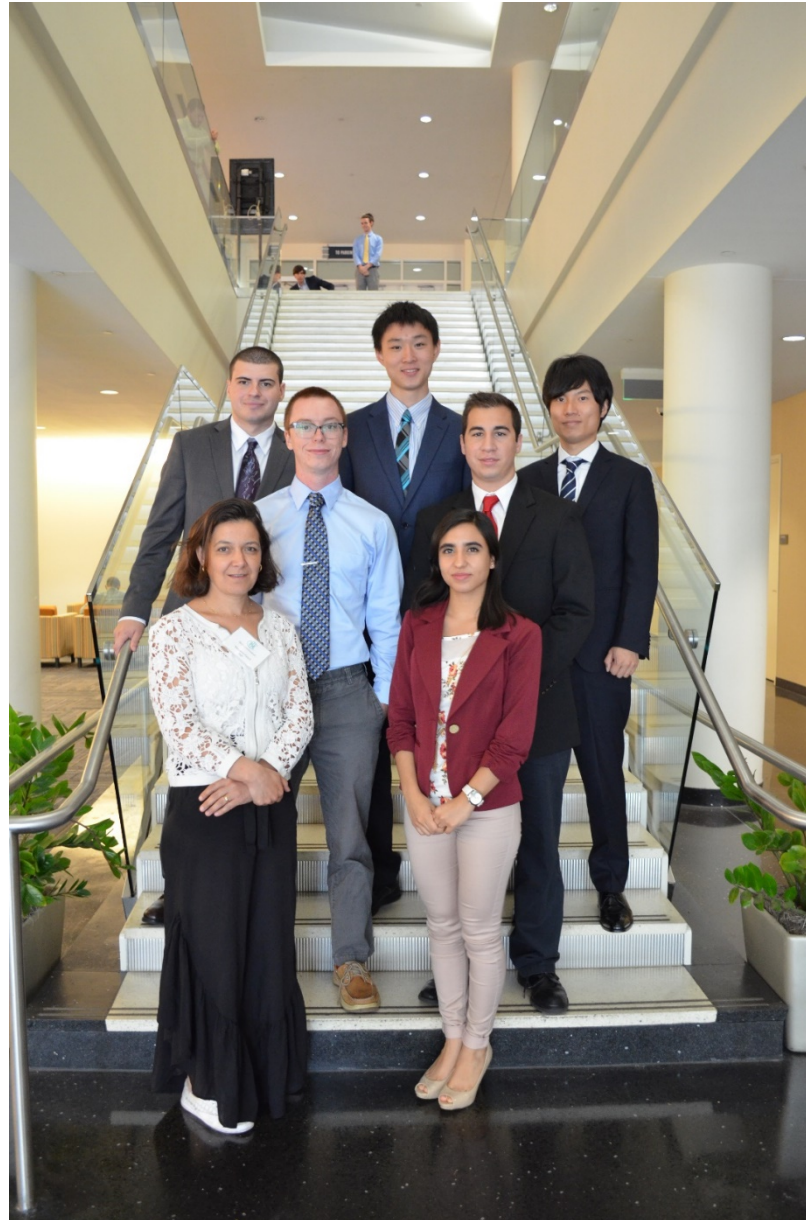
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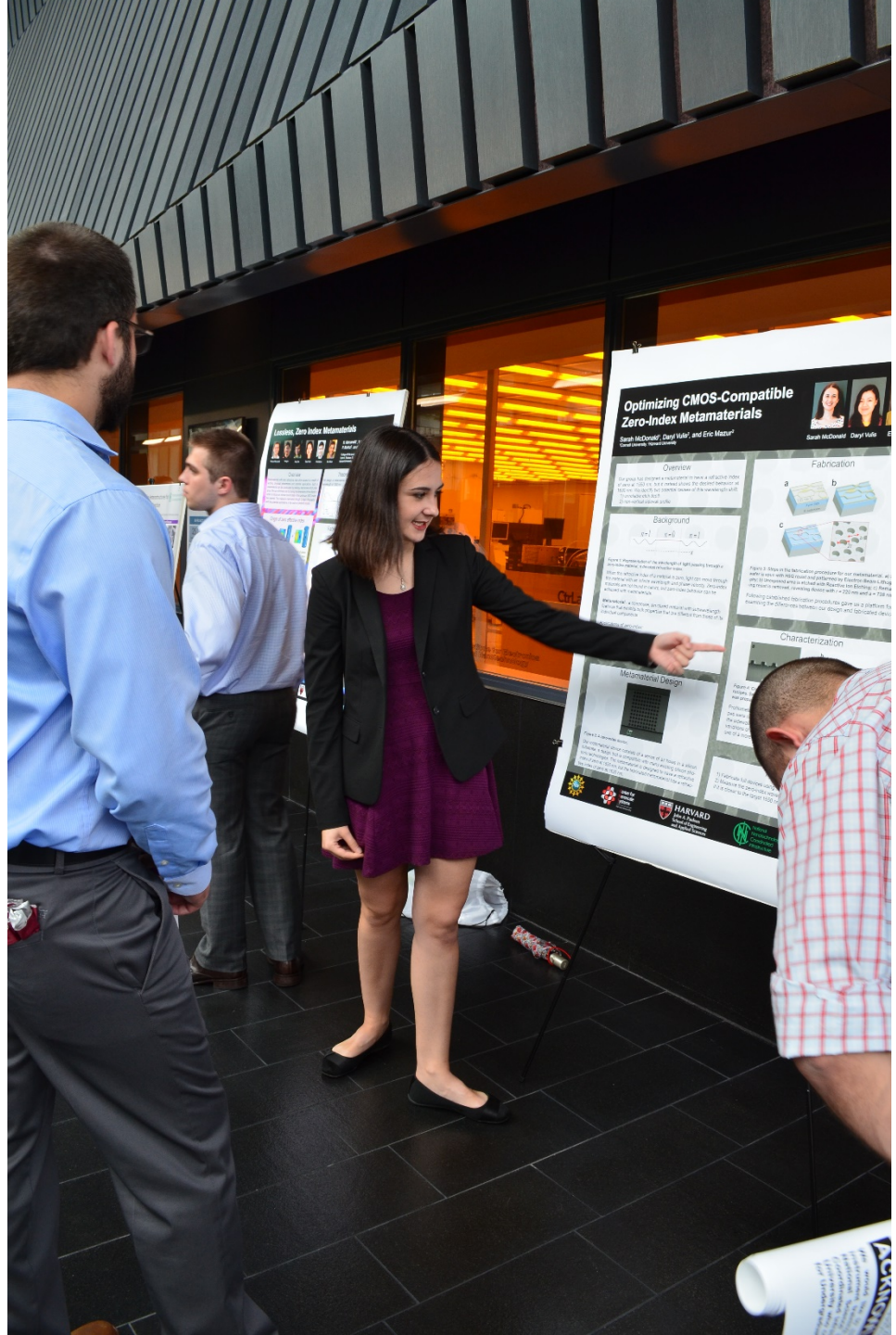


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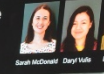
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Optimizing CMOS-Compatible Zero-Index Metamaterials

Sarah McDonald, David Hahn, and Eric Mazur



Overview

The goal of this research is to design a zero-index metamaterial that can be fabricated using CMOS-compatible processes. This is achieved by using a combination of dielectric and metallic materials to create a structure with a refractive index of zero.

Background

Zero-index metamaterials have a refractive index of zero, which allows them to focus light into a sub-wavelength spot. This property is useful for applications in photonic integrated circuits and quantum computing.

Metamaterial Design

The design of the metamaterial involves the optimization of the geometry and material properties of the structure. This is done using a combination of analytical and numerical methods.

Fabrication

The metamaterials are fabricated using a combination of dielectric and metallic materials. The dielectric part is fabricated using a CMOS-compatible process, while the metallic part is fabricated using a separate process.

Figure 1 shows the fabrication process for the metamaterials. The process involves the deposition of a dielectric layer, followed by the deposition of a metallic layer. The metallic layer is then patterned to create the desired structure.

Figure 2 shows the characterization of the metamaterials. The characterization is done using a combination of analytical and numerical methods. The results show that the metamaterials have a refractive index of zero, as expected.

Figure 3 shows the characterization of the metamaterials. The characterization is done using a combination of analytical and numerical methods. The results show that the metamaterials have a refractive index of zero, as expected.

Characterization

The characterization of the metamaterials is done using a combination of analytical and numerical methods. The results show that the metamaterials have a refractive index of zero, as expected.

Metamaterial Design

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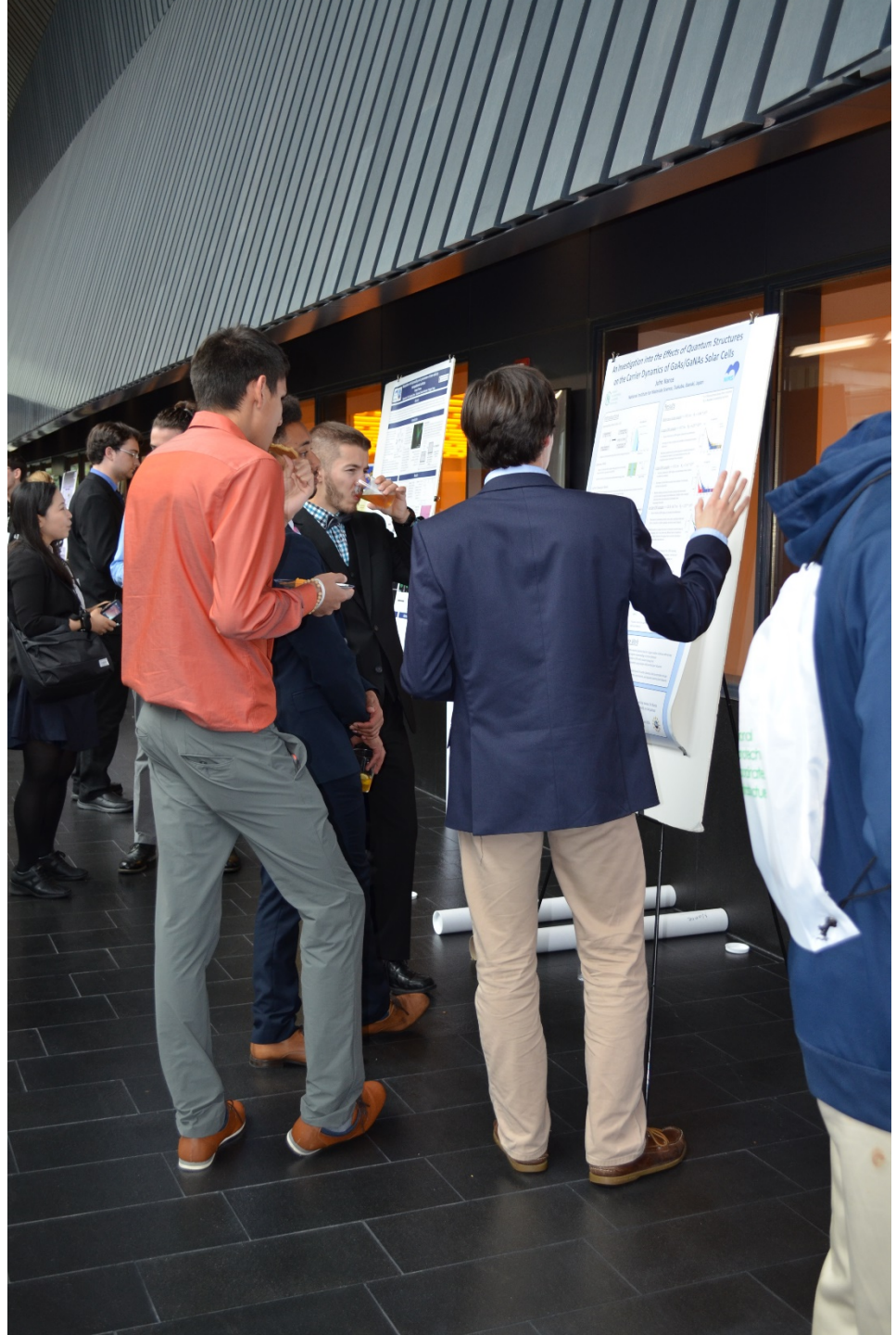
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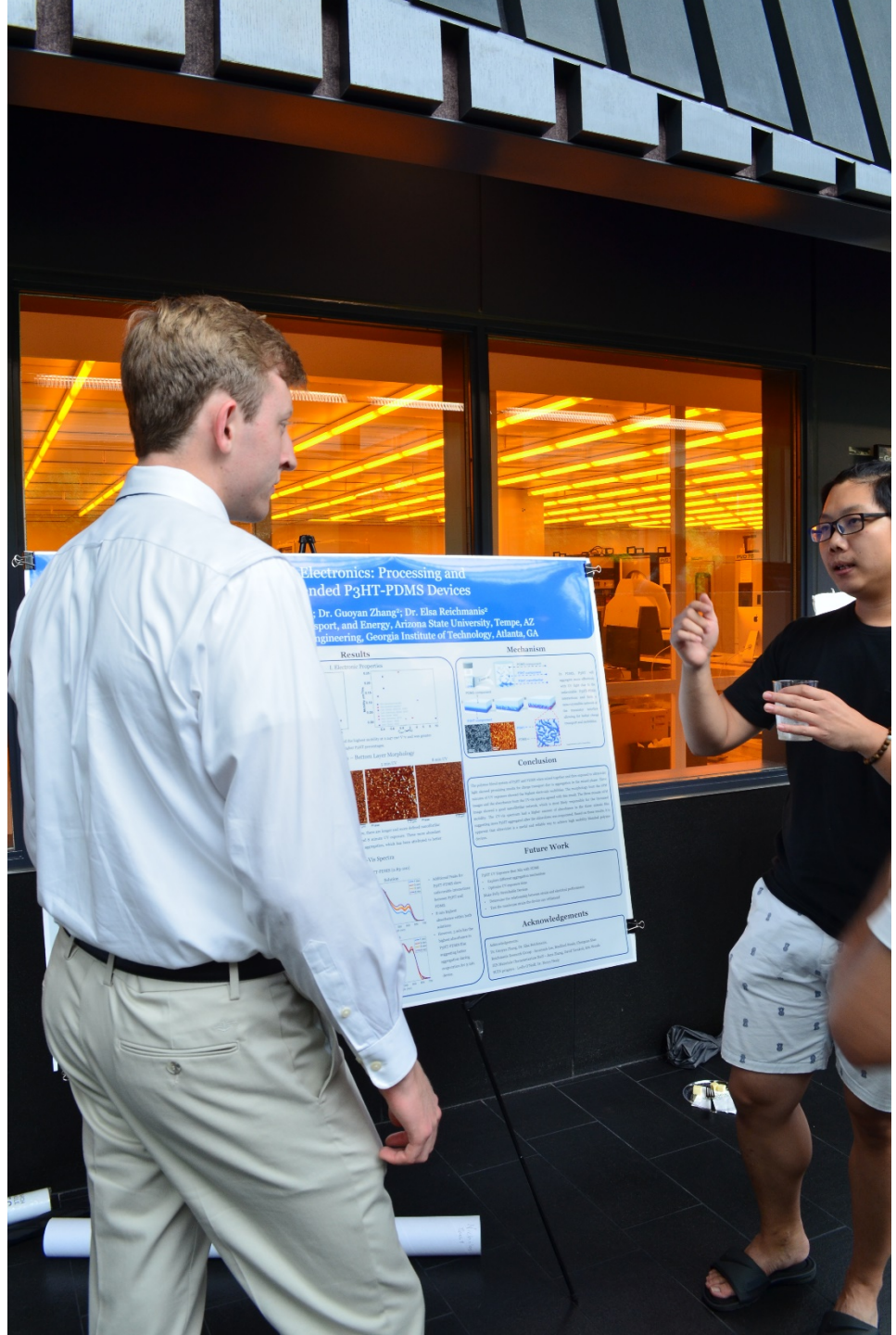
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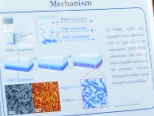
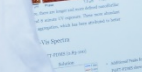
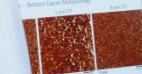
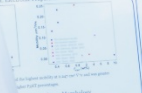




Electronics: Processing and Integrated P3HT-PDMS Devices

Dr. Guoyan Zhang*, Dr. Elsa Reichmanis*
Department of Electrical and Energy, Arizona State University, Tempe, AZ
School of Chemical and Biomolecular Engineering, Georgia Institute of Technology, Atlanta, GA

Results



Mechanism
The P3HT-PDMS devices exhibit a unique mechanism of operation. The P3HT layer acts as a charge transport channel, while the PDMS layer provides a dielectric environment. The interaction between the P3HT and PDMS layers leads to the formation of a charge transport channel, which is responsible for the device's performance.

Conclusion
The P3HT-PDMS devices show promising performance characteristics, including high current density and low power consumption. The unique mechanism of operation, involving the interaction between the P3HT and PDMS layers, is a key factor in the device's performance.

Future Work
Future work will focus on optimizing the device structure and materials to further improve performance. This includes exploring different device geometries and materials for the P3HT and PDMS layers.

Acknowledgements
This work was supported by the National Science Foundation (NSF) Grant [Number]. We thank [Name] for their assistance in the laboratory.



High Performance Circuit Boards for Microelectronics

Spencer C. Temples¹, Jisu Jiang², Paul A. Kohl²

¹ School of Chemical and Biomolecular Engineering, Clemson University, Clemson, S.C.;
² School of Chemical and Biomolecular Engineering, Georgia Institute of Technology, Atlanta, GA

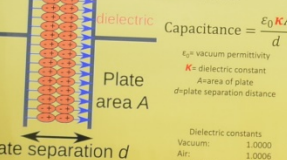
Background

Dielectrics and Parasitic Capacitance

Microelectronics in close proximity act as parasitic capacitors, draining the system of energy.

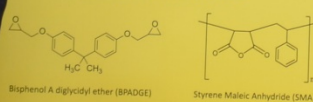
As electronics shrink, the distance (d) between components get smaller which increases capacitance.

The dielectric constant (κ) must be lowered to compensate and maintain a low parasitic capacitance.

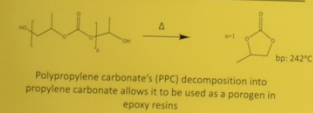


Epoxy Resins and Microelectronics

Epoxy Resins are widely used for the manufacturing of printed circuit boards, as they are cheap and durable.



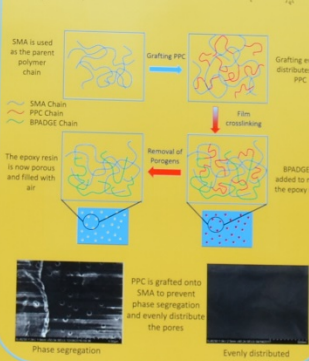
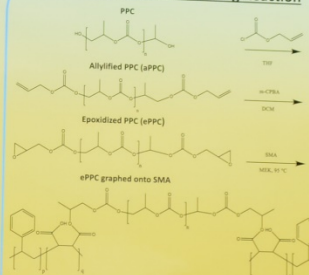
Polypropylene Carbonate Decomposition



Polypropylene carbonate's (PPC) decomposition into propylene carbonate allows it to be used as a porogen in epoxy resins.

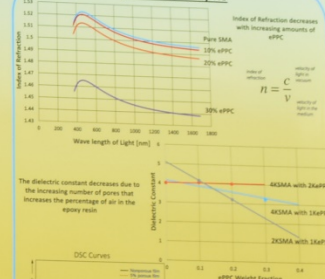
Methodology

Functionalization and Grafting Reaction



Results

Data and Graphs



Conclusions and Future Work

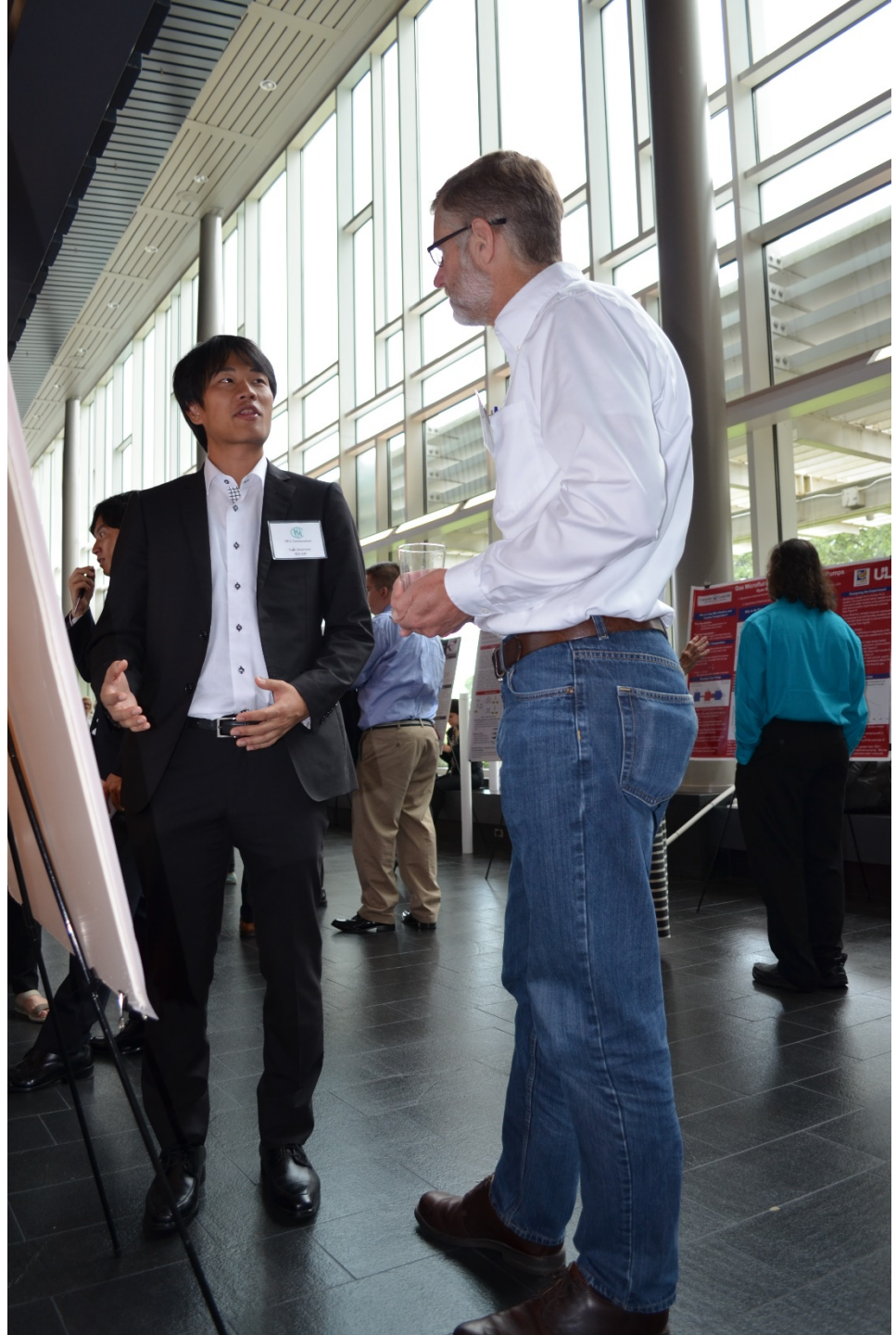
The dielectric constant, index of refraction, and glass transition temperature all decreased with increasing porosity.

Analyze samples for residual propylene carbonate that may have an effect on dielectric constant.

Measure mechanical properties to determine the effect of increasing porosity.

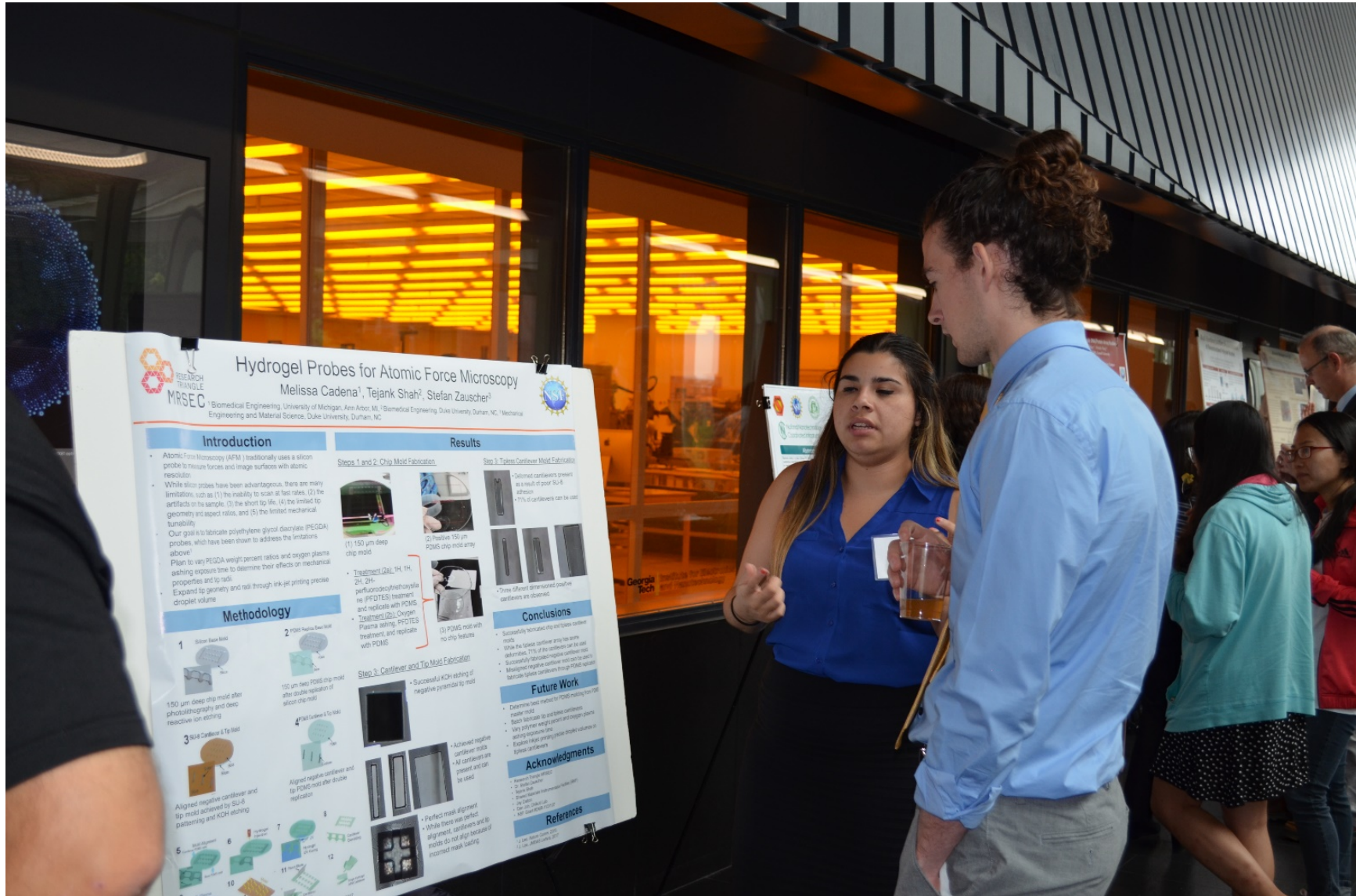
Acknowledgements











Hydrogel Probes for Atomic Force Microscopy

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¹Biomedical Engineering, University of Michigan, Ann Arbor, MI; ²Biomedical Engineering, Duke University, Durham, NC; ³Mechanical Engineering and Material Science, Duke University, Durham, NC

Introduction

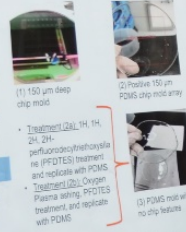
Atomic Force Microscopy (AFM) traditionally uses a silicon probe to measure forces and image surfaces with atomic resolution. While silicon probes have been advantageous, there are many limitations, such as (1) the inability to scan at fast rates, (2) the artifacts on the sample, (3) the short tip life, (4) the limited tip geometry and aspect ratios, and (5) the limited mechanical tunability. Our goal is to fabricate polyethylene glycol diacrylate (PEGDA) probes which have been shown to address the limitations above. Plan to vary PEGDA weight percent ratios and oxygen plasma ashing exposure time to determine their effects on mechanical properties and tip radii. Expand tip geometry and radii through ink-jet printing precise droplet volume.

Methodology



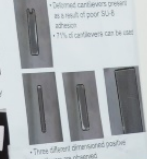
Results

Steps 1 and 2: Chip Mold Fabrication



(1) 150 μm deep chip mold
(2) Positive 150 μm PDMS chip mold array
(3) PDMS mold with no chip features

Step 3: Cantilever Mold Fabrication



• Deformed cantilevers present as a result of poor SU-8 adhesion
• 71% of cantilevers can be used
• Three different dimensional positive cantilevers are observed

Step 3: Cantilever and Tip Mold Fabrication



• Successful KOH etching of negative pyramidal tip mold
• Achieved negative cantilever molds
• All cantilevers are present and can be used
• Perfect mask alignment
• While there are perfect alignment, cantilevers and tip molds do not align because of incorrect mask usage

Conclusions

• Successfully fabricated chip cantilever molds
• While the silicon cantilever array has been achieved, 71% of the cantilevers can be used
• Successfully fabricated negative cantilever mold
• Managed negative cantilever and tip mold fabrication
• Manage tip geometry and aspect ratios

Future Work

• Determine best method for PDMS coating from top master mold
• Each cantilever tip and base cantilevers
• Very poor alignment between cantilever and tip
• Establish high printing volume production volume in glass cantilevers

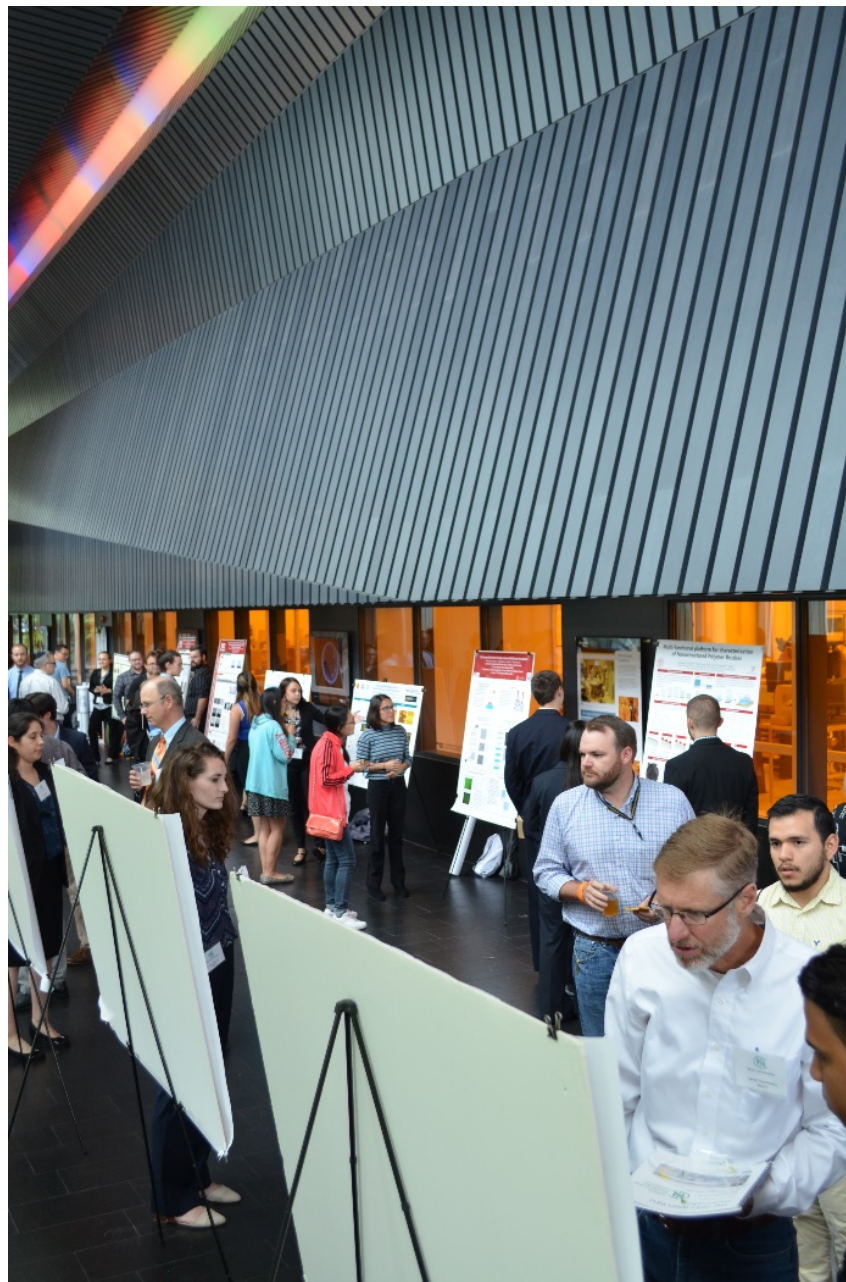
Acknowledgments

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• Dr. Michael J. Buehler
• Dr. Michael J. Buehler
• Dr. Michael J. Buehler

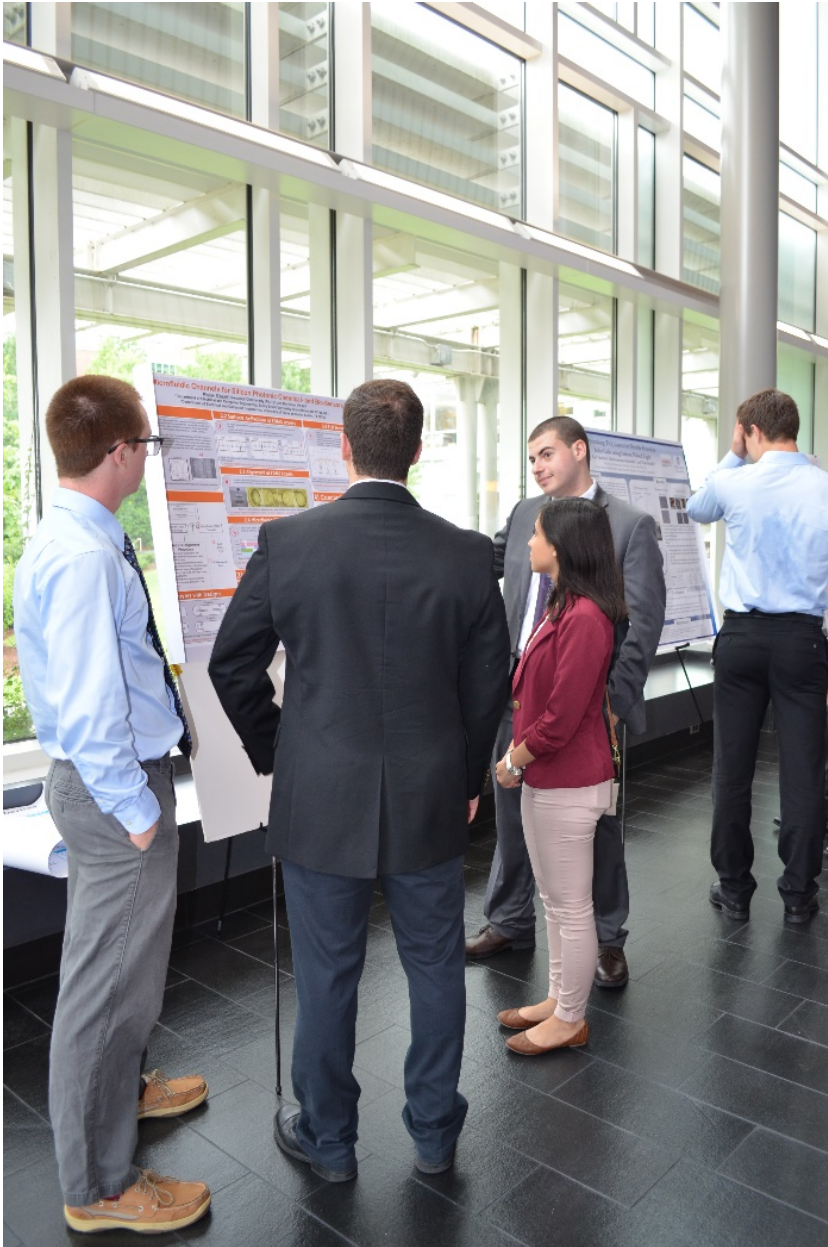
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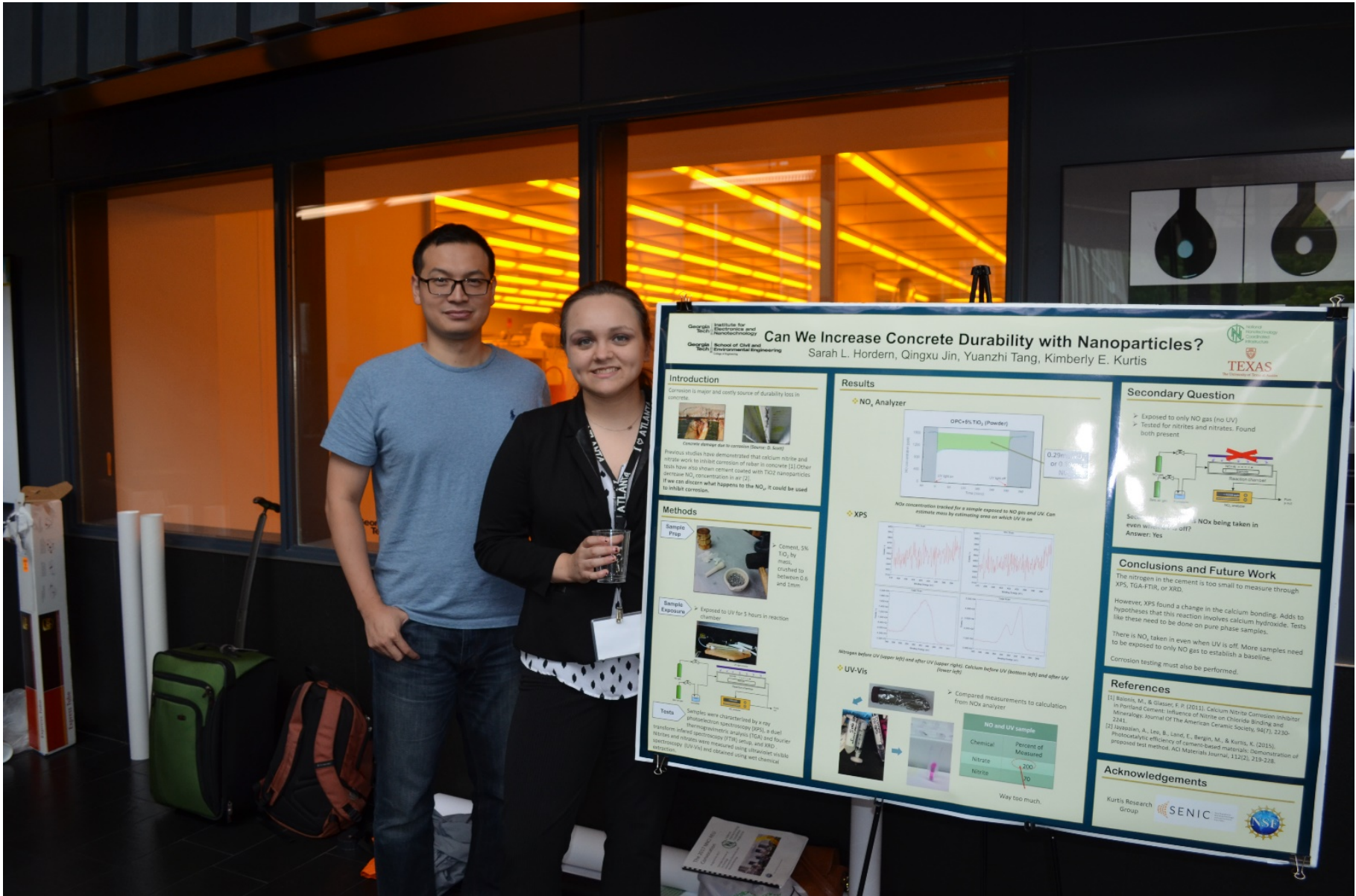
1. Lee, M. S., et al. (2011).
2. Lee, M. S., et al. (2011).











Can We Increase Concrete Durability with Nanoparticles?
 Sarah L. Hordern, Qingxu Jin, Yuanzhi Tang, Kimberly E. Kurtis

Georgia Institute of Technology
 School of Architecture and
 Environmental Engineering

Georgia Institute of Technology
 School of Civil and
 Environmental Engineering

TEXAS
 A&M UNIVERSITY

Introduction
 Corrosion is major and costly source of durability loss in concrete.
 Previous studies have demonstrated that calcium nitrite and nitrate work to inhibit corrosion of rebar in concrete [1] Other tests have also shown cement coated with TiO₂ nanoparticles [2]. If we can discern what happens to the NO_x, it could be used to inhibit corrosion.

Methods
Sample Prep
 Cement, 5% TiO₂ by mass, crushed to between 0.8 and 1mm
Sample Exposure
 Exposed to UV for 5 hours in reaction chamber
Tests
 Samples were characterized by a ray photoelectron spectroscopy (XPS), a dual beam infrared spectrometry (FTIR), and Fourier Transform Infrared Spectrometry (FTIR) analysis. Nitrite and nitrate were measured using colorimetric visible spectroscopy (UV-Vis) and obtained using wet chemical analysis.

Results
NO_x Analyzer
 OPC-6%TiO₂ (Powder)
 0.2% NO_x or 0.1% NO_x
 NO_x concentration tracked for a sample exposed to NO gas and UV. Can estimate mass by estimating area on which UV is on.
XPS
 Nitrogen before UV (upper left) and after UV (upper right); Calcium before UV (bottom left) and after UV (lower left)
UV-Vis
 Compared measurements to calculation from NO_x analyzer
 Way too much.

Secondary Question
 Exposed to only NO gas (no UV)
 Tested for nitrites and nitrates. Found both present
 Secondary Question: NO_x being taken in even without UV?
 Answer: Yes

Conclusions and Future Work
 The nitrogen in the cement is too small to measure through XPS, TGA-FTIR, or XRD.
 However, XPS found a change in the calcium bonding. Adds to hypotheses that this reaction involves calcium hydroxide. Tests like these need to be done on pure phase samples.
 There is NO_x taken in even when UV is off. More samples need to be exposed to only NO gas to establish a baseline.
 Corrosion testing must also be performed.

References
 [1] Balonis, M., & Gosson, F. P. (2011). Calcium Nitrite Corrosion Inhibitor in Portland Cement: Influence of Nitrite on Chloride Binding and 2241. *Mineralogy Journal of The American Ceramic Society*, 94(7), 2230-2241.
 [2] Iyavassan, A., Lee, B., Lind, E., Bergin, M., & Kurtis, K. (2015). Photoanalytic efficiency of cement-based materials: Demonstration of proposed test method. *ACI Materials Journal*, 112(2), 219-228.

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